	L#	Hits	Search Text	D	Time Stamp
1	L1	0	micron.asn	USPAT; EPO; JPO	2000/11/15 18:36
2	L5	6917	micron.asn.	USPAT; EPO; JPO	2000/11/15 18:36
3	L9	1775	wet adj oxidation	USPAT; EPO; JPO	2000/11/15 18:37
4	L13	68	5 and 9	USPAT; EPO; JPO	2000/11/15 18:52
5-	L17 -	9	13-and-rapid	USPAT; EPO; JPO	2000/11/15 19:44
6	L21	4	13 and RTO	USPAT; EPO; JPO	2000/11/15 19:53
7	L25	3	13 and RTP	USPAT; EPO; JPO	2000/11/15 19:51
8	L29	5240	(oxidiz\$3 or oxidation) near10 wet	USPAT; EPO; JPO	2000/11/15 20:42
9	L33	28852	(oxidiz\$3 or oxidation) near10 water	USPAT; EPO; JPO	2000/11/15 19:55
10	L37	6234	(oxidiz\$3 or oxidation) near10 steam	USPAT; EPO; JPO	2000/11/15 19:55
11	L41	6642	(oxidiz\$3 or oxidation) near10 "H.sub.2"	USPAT; EPO; JPO	2000/11/15 20:42
12	L45	2632	(oxidiz\$3 or oxidation) near10 moisture	USPAT; EPO; JPO	2000/11/15 19:55
13	L49	43709	29 33 37 41 45	USPAT; EPO; JPO	2000/11/15 19:56
14	L53	2110	oxygen near3 deficient	USPAT; EPO; JPO	2000/11/15 19:57
15	L57	229	49 and 53	USPAT; EPO; JPO	2000/11/15 19:57
16	L61	28	49 same pinhole!	USPAT; EPO; JPO	2000/11/15 20:44
17	L65	98	57 and (RTA or RTP or RTO or rapid)	USPAT; EPO; JPO	2000/11/15 20:43
18	L69	660	anneal\$3 near10 wet	USPAT; EPO; JPO	2000/11/15 20:42
19	L73	1939	anneal\$3 near10 water	USPAT; EPO; JPO	2000/11/15 20:42
20	L77	336	anneal\$3 near10 steam	USPAT; EPO; JPO	2000/11/15 20:42
21	L81	226	anneal\$3 near10 moisture	USPAT; EPO; JPO	2000/11/15 20;42
22	L85	672	anneal\$3 near10 "H.sub.2"	USPAT; EPO; JPO	2000/11/15 20:43
23	L89	3482	69 73 77 81 85	USPAT; EPO; JPO	2000/11/15 20:43
24	L93	850	89 and (RTA or RTP or RTO or rapid)	USPAT; EPO; JPO	2000/11/15 20:49
25	L97	13	93 and pinhole!	USPAT; EPO; JPO	2000/11/15 20:44
26	L101	107	89 and (RTA or RTP or RTO)	USPAT; EPO; JPO	2000/11/15 20:49